

NEWS RELEASE

Hitachi High-Tech

HITACHI

Hitachi High-Technologies Corporation

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Hitachi High-Tech Sues FEI Japan for Patent Infringement

On August 19, 2011, Hitachi High-Technologies Corporation (TOKYO:8036, Hitachi High-Tech) filed a lawsuit against FEI Japan at the Tokyo District Court, claiming damages for infringement of Japanese Patent No. 2,774,884* related to the Micro-Sampling technology using Focused Ion Beam, taking the effective period of the same patent into consideration.

Hitachi High-Technologies considers its intellectual property rights as extremely important management resources, and will make every effort to protect such rights.

[Note]

Japanese Patent No. 2,774,884: On August 12, 2011, Intellectual Property High Court dismissed the appeal filed by FEI Japan. On June 5, 2011, Tokyo District Court made a preliminary injunction order against FEI Japan to stop manufacture, sale and import of Quanta 3DFEG (Equipped with a probe (Omni probe or Auto probe) and GIS apparatus with Platinum Deposition gas, Tungsten Deposition gas, or Carbon Deposition gas). FEI Japan filed an objection to this preliminary injunction order and has filed an appeal before the Intellectual Property High Court. Intellectual Property High Court accepted the preliminary injunction order against FEI Japan and dismissed FEI Japan's appeal.

*GIS apparatus: Gas Injection System

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